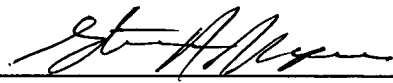


been made or that no other material information as defined in 37 C.F.R. § 1.56(b) exists.

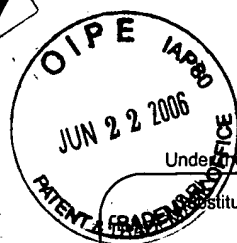
Applicants respectfully request that the Examiner review the foregoing references and request that they be made of record in the file history of the above-captioned application.

A check in the amount of \$180.00 is enclosed as required under 37 CFR 1.17(p). The Commissioner is hereby authorized to charge any fee, including any submitted herewith if the attached check(s) is in the wrong amount or otherwise improper or missing, that may be due in connection with this and the attached papers, or with this application during its entire pendency to or to credit any overpayment to Deposit Account No. 50-1213. A duplicate of this sheet is enclosed.

Respectfully submitted,
HELLER EHRMAN LLP

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Sheet 1 of 8

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Application Number	10/765,223
Filing Date	01/26/2004
First Named Inventor	Smith et al
Art Unit	1756
Examiner Name	C. Young
Attorney Docket Number	38203-6081B

U. S. PATENT DOCUMENTS

Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code ² (if known)			
		US- 4,757,207	07/1988	Chappelow et al	
		US- 4,861,148	08/1989	Sato et al	
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		US- 5,894,350	04/1999	Hsieh et al	
		US- 6,259,525	07/2001	David	
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Attorney Docket Number	38203-6081B

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Examiner Name	C. Young
Attorney Docket Number	38203-6081B

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